

SUBSTRATE PROCESSING APPARATUS AND TRAY

ABSTRACT

In a substrate processing apparatus, sheath control of a substrate outer peripheral portion is appropriately performed, and a consumption amount of an annular portion of a tray is appropriately controlled. The substrate processing apparatus for processing a substrate, includes: a processing chamber; and a support member disposed within the processing chamber and having a tray support surface for supporting the tray on an upper surface thereof. The tray includes a base portion and a peripheral edge that forms a recess configured to accommodate the substrate on an upper surface of the base portion, and the base portion and the peripheral edge are configured separately from each other.

Figure 14